

Ion-Beam Milling - RFICP140

- Etching of **film (metal, oxides, a-Si:H, etc.)**
- Gas: Ar
- Discharge type: RFICP
- Max. Discharge Power: >600W
- Beam Current: >500mA
- Pressure: < 0.5mTorr
- Voltage range: 100-1200 V
- Typical gas (Ar) Flow : 5-40sccm

